(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization International Bureau



(43) International Publication Date 7 October 2004 (07.10.2004)

(10) International Publication Number WO 2004/085706 A1

(51) International Patent Classification7: 3/06, H01L 21/3213

C23F 1/18,

(21) International Application Number:

PCT/EP2004/002702

(22) International Filing Date: 16 March 2004 (16.03.2004)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

103 13 517.0

25 March 2003 (25.03.2003)

- (71) Applicant (for all designated States except US):

- (81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.
- (84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR,

(71) Applicant (for all designated States except US):
ATOTIECH DEUTSCHLAND GMBH [DE/DE];
Erasmustrasse 20, 10533 Berlin (DE).

(72) Inventors; and
(73) Inventors; and
(75) Inventors/Applicants (for US only): MAHLKOW, Hartmut (DE/DE); Handjerystrasse 85, 12159 Berlin (DE).

SPARING, Christian [DE/DE]; Ernststrasse 95, 13509
Berlin (DE).

(74) Agent: EFFERT, BRESSEL UND KOLLEGEN; Radickestrasse 48, 12489 Berlin (DE).

(75) Abstract: A solution for etching copper or a copper alloy for producing a copper surface having the brightest possible finish for a metallization that is to follow is described. The solution has a pH on the order of 4 or less and is free of sulfate ions. It comprises: a) at least one oxidizing agent selected from the group comprising marmatic sulfonic acids and salts of the aromatic sulfonic acids and optonic acids and optonially of least one N-heterocyclic compound. Further a method for depositing metal onto the surface of copper or a copper alloy is described. Salt on the surface of copper or a copper alloy is described. Salt on the surface of with at least one metal. The solution and the method are especially suited in the production of electric circuit method comprises the following method steps: a) contacting the surface with the solution in accordance with the invention and b) coating the surface with at least one metal. The solution and the method are especially suited in the production of electric circuit carriers, more specifically for semiconductor manufacturing.

